

Test Report

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穩懋半導體股份有限公司 WIN SEMICONDUCTORS CORP.

桃園市龜山區華亞科技園區科技七路35號

NO.35, KEJI 7TH RD., HWAYA TECHNOLOGY PARK, GUISHAN DISTRICT, TAOYUAN CITY 33383, TAIWAN

以下測試樣品係由申請廠商所提供及確認 (The following sample(s) was/were submitted and identified by/on behalf of the applicant as):

送樣廠商(Sample Submitted By) 穩懋半導體股份有限公司 (WIN SEMICONDUCTORS CORP.)

樣品名稱(Sample Description) HBT WAFER 收件日期(Sample Receiving Date) 2019/10/21

測試期間(Testing Period) 2019/10/21 to 2019/10/28

測試結果(Test Results) : 請參閱下一頁 (Please refer to following pages).

Troy Chang / Manager - Teq Signed for and behalf of SĞS TAIWAN LTD. Chemical Laboratory - Taipei





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測試結果(Test Results)

測試部位(PART NAME)No.1 晶圓 (WAFER)

測試項目 (Test Items)	單位 (Unit)	測試方法 (Method)	MDL	結果 (Result) No.1
全氟辛烷磺酸 / Perfluorooctane sulfonates (PFOS-Acid, Metal Salt, Amide)	mg/kg	參考CEN/TS 15968 (2010),以液相層析/質譜儀檢測. / With reference to CEN/TS 15968 (2010). Analysis was performed by LC/MS.	0.01	n. d.
全氟辛酸 / PFOA (CAS No.: 335-67-1)	mg/kg	参考CEN/TS 15968 (2010),以液相層析/質譜儀檢測. / With reference to CEN/TS 15968 (2010). Analysis was performed by LC/MS.	0. 01	n. d.
銻 / Antimony (Sb)	mg/kg	参考US EPA 3050B (1996),以感應耦合電漿發射光譜儀檢測. / With reference to US EPA 3050B (1996). Analysis was performed by ICP-OES.	2	n. d.
鈹 / Beryllium (Be)	mg/kg	參考US EPA 3050B (1996),以感應耦合電漿發射光譜儀檢測. / With reference to US EPA 3050B (1996). Analysis was performed by ICP-OES.	2	n. d.

備註(Note):

- 1. mg/kg = ppm ; 0.1wt% = 1000ppm
- 2. MDL = Method Detection Limit (方法偵測極限值)
- 3. n.d. = Not Detected (未檢出)



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PFOS参考資訊(Reference Information): 持久性有機污染物 POPs - (EU) 2019/1021

PFOS濃度在物質或製備中不得超過0,001%(10ppm),在半成品、成品或零部件中不得超過0,1%(1000ppm),在紡織品或塗 層材料中不得超過1µg/m²。

(Outlawing PFOS as substances or preparations in concentrations above 0.001% (10ppm), in semi-finished products or articles or parts at a level above 0.1%(1000ppm), in textiles or other coated materials above $1\mu g/m^2$.)



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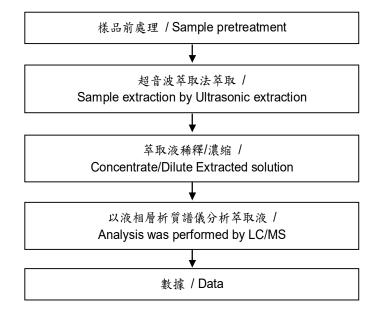
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全氟辛酸/全氟辛烷磺酸分析流程圖 / Analytical flow chart - PFOA/PFOS

■ 測試人員:涂雅苓 / Technician: Yaling Tu

測試負責人:張啟興 / Supervisor: Troy Chang





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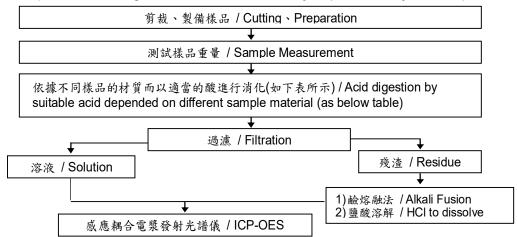
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根據以下的流程圖之條件,樣品已完全溶解。 / These samples were dissolved totally by pre-conditioning method according to below flow chart.

測試人員:陳恩臻 / Technician: Rita Chen

測試負責人:張啟興 / Supervisor: Troy Chang

元素以 ICP-OES 分析的消化流程圖 (Flow Chart of digestion for the elements analysis performed by ICP-OES)



鋼,銅,鋁,焊錫 / Steel, copper, aluminum, solder	王水,硝酸,鹽酸,氫氟酸,雙氧水 / Aqua regia, HNO ₃ , HCI, HF, H ₂ O ₂
玻璃 / Glass	硝酸,氫氟酸 / HNO ₃ /HF
金,鉑,鈀,陶瓷 / Gold, platinum, palladium, ceramic	王水 / Aqua regia
銀 / Silver	硝酸 / HNO ₃
塑膠 / Plastic	硫酸,雙氧水,硝酸,鹽酸 / H ₂ SO ₄ , H ₂ O ₂ , HNO ₃ , HCI
其他 / Others	加入適當的試劑至完全溶解 / Added appropriate reagent to total digestion



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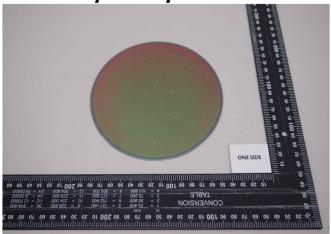
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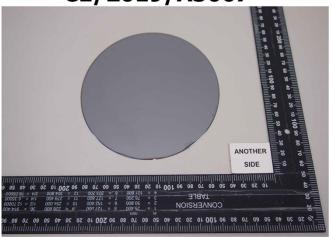
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* 照片中如有箭頭標示,則表示為實際檢測之樣品/部位. * (The tested sample / part is marked by an arrow if it's shown on the photo.)

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** 報告結尾 (End of Report) **